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B.S., 1956 and M.A., 1960, both in Mathematics, University of Detroit; Graduate work in math, 1960–1963, Wayne State University. Was a mathematical analyst at Bendix Aviation from 1956 to 1958. Joined IBM in 1963 at Endicott to work in the area of scientific programming. Currently, working in the advanced programming technology area, engaged in the development of programs to employ graphic devices as design aids for scientists and engineers. Member, Mathematical Association of America, and Association for Computing Machinery.

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B.S. in Electrical Engineering, 1953, Taiwan University; Ph.D. in Electrical Engineering, 1960, University of Illinois. Was a part-time Instructor in the Department of Electrical Engineering at the University of Illinois from 1955 to 1960. Joined IBM at the Research Center in 1960 and has been a member of the research staff in the Department of Applied Research. He lectured at the Stamford Extension of the University of Connecticut in 1965, and was on leave of absence as a visiting professor at the National Taiwan University, 1965–66. His research interests include network approximation, communication networks, graph theory, magnetic recording, and coding theory. Member, Eta Kappa Nu, Sigma Xi, and IEEE.

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